

	Type	L #	Hits	Search Text	DBs
1	BRS	L1	515	("etch stop" or "hard mask" or barrier) near7 ((undoped or doped) near7 ("SiO.sub.2" or SiO2 or "silicon oxide" or oxide or dioxide or "silicon dioxide"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
2	BRS	L2	404	@ad<=20000901 and 1	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
3	BRS	L3	27	damascene and 2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB